

CLAIMS:

1. A thermal treatment apparatus comprising:
 - a furnace of a refractory;
 - a stage capable of carrying synthetic silica glass and moving between a first stage position for letting the synthetic silica glass into the furnace and a second stage position for letting the synthetic silica glass out of the furnace;
 - a heat generator for heating the synthetic silica glass; and
 - a driving section connected to the stage, for moving the stage between the first stage position and the second stage position.
2. A thermal treatment apparatus according to claim 1, further comprising a rotational driving section for rotating the stage.